



Low Temperature Integration of Hybrid CMOS Devices on Plastic Substrates

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- Processing Details
- CMOS Performance
 - NAND, NOR Gates
 - Inverters
- CMOS Reliability
 - Electron and hole Mobility
 - V_t stability
 - Electrical Stress induced degradation
- Summary

- Substrates evaluated
 - Thermally stabilized PEN
 - Stainless steel
- Maximum processing temperature: 180°C (nMOS) and 120°C (PMOS)
- Fabrication of a:Si:H-based nMOS devices first, followed by the pentacene-based pMOS devices.
 - a:Si:H TFTs,
 - molybdenum as the gate metal
 - Si₃N₄ as the gate dielectric
 - Aluminum as the source-drain contacts
 - Pentacene- OTFT
 - Aluminum gate the metal
 - Parylene as gate insulator and inter-level dielectric
 - Gold electrodes as source-drain contacts
- The circuits are encapsulated using parylene for passivation with vias opened for device testing.

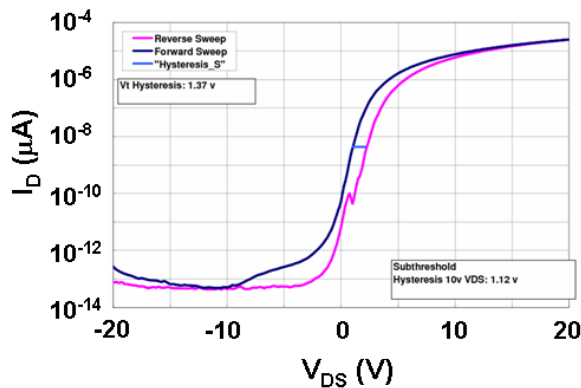
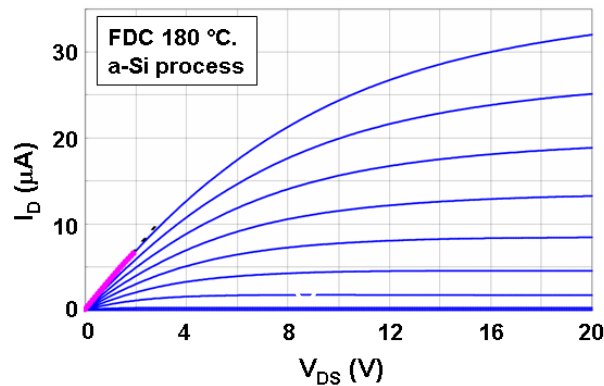
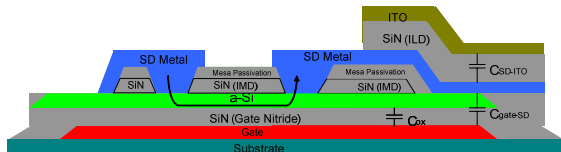
Authors	Dielectric	Mean V_t (V)	V_{Tt} Std.Dev ($\pm V$)	% Std.Dev of V_T
K.P. Pernstich [1]	SiO ₂ / OTS	-3.7	1.0	27
I. Kymissis [2]	Parylene	-3.5	1.0	29
K. Diallo [3]	Parylene	-3.5	Not reported	Not reported
J. Puidgollers [4]	PMMA	-15	Not reported	Not reported
This work	Parylene	-2.3	0.27	12

SiO ₂ / HMDS / Pentacene	Parylene / Pentacene
<ul style="list-style-type: none"> • Water contact angle = 60-90° • Unreacted OH on SiO₂ with HMDS/OTS shifts V_T • Complex, time consuming and batch-batch variation in preparing solution • V_T variation > 35% 	<ul style="list-style-type: none"> • Water contact angle = 100-105° • OH free surface provides less V_T variation • Simple CVD process • V_T variation < 15% (easier to design circuits with stable gate overdrive)

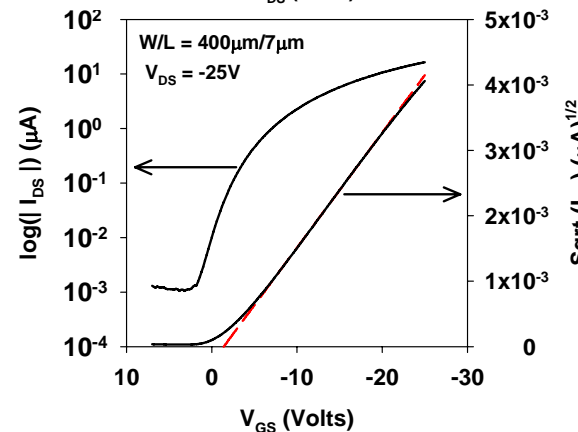
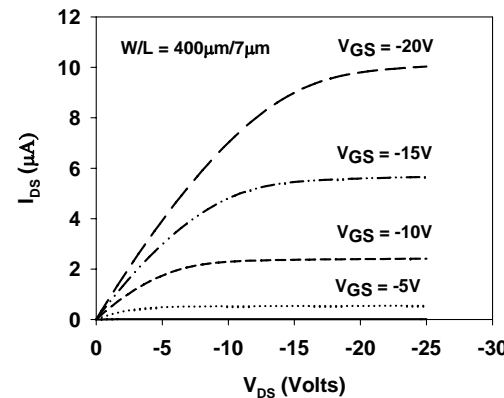
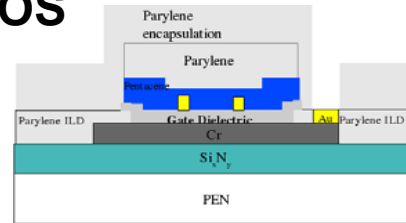
- Using parylene as the gate dielectric allows V_t variation to < 15%
- Low V_t variation critical for circuit design..

[1] J. Appl. Phys. **96**, 11 (2004), [2] Journal of Display Technology **1**, 2 (2005), [3] Appl. Phys. Lett. **91**, 183508 (2007), [4] Organic Electronics **5**, 67 (2004).

NMOS



PMOS

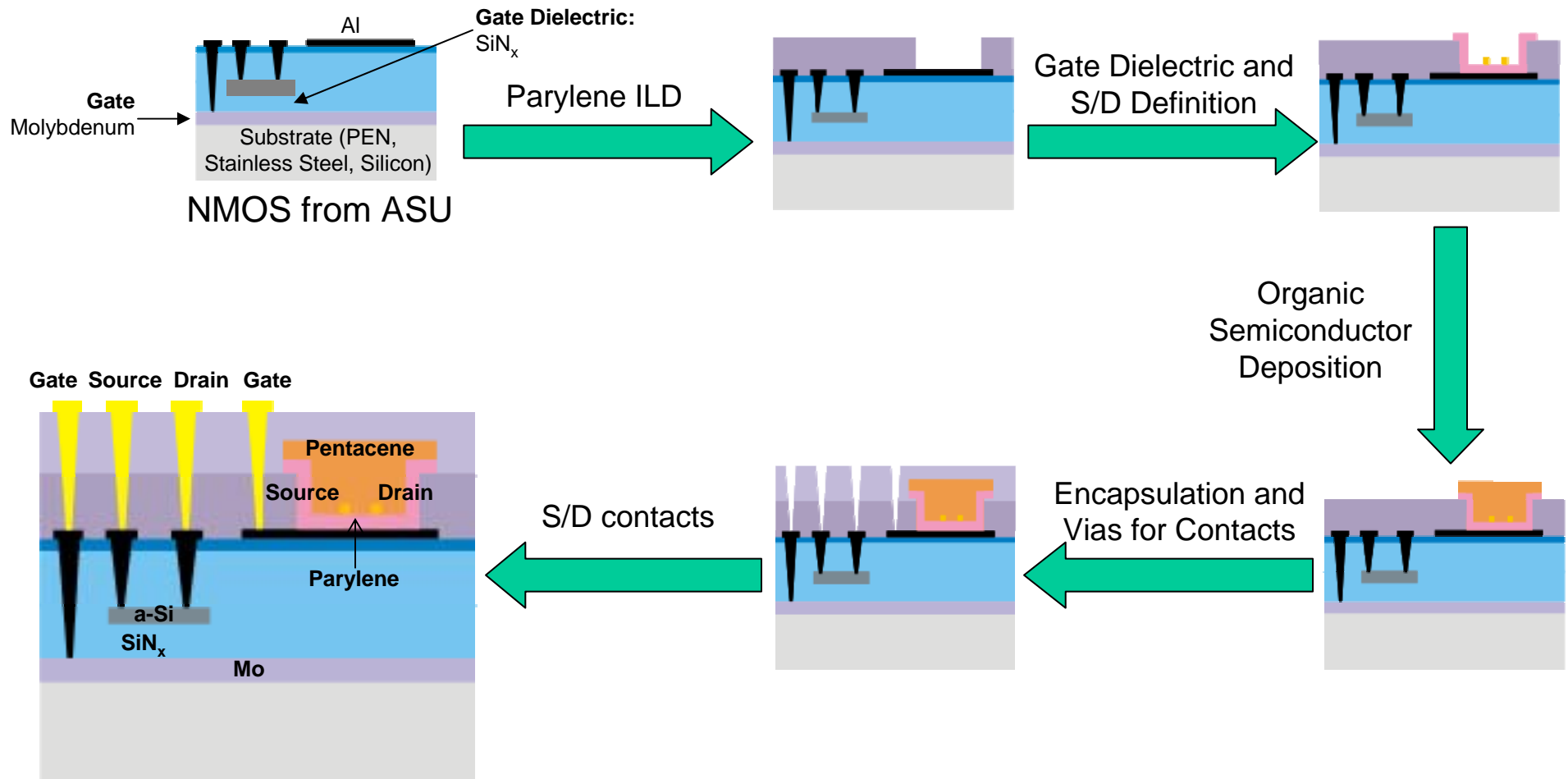


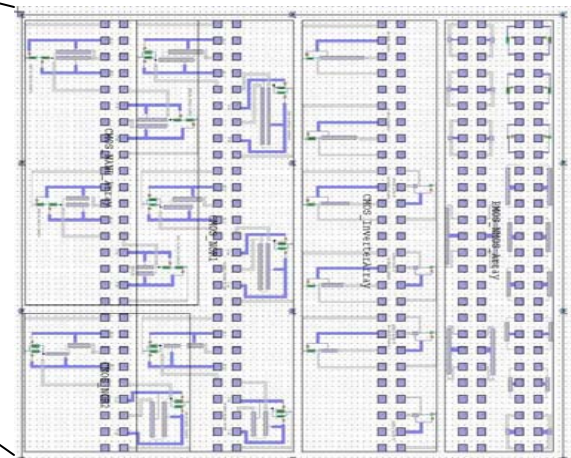
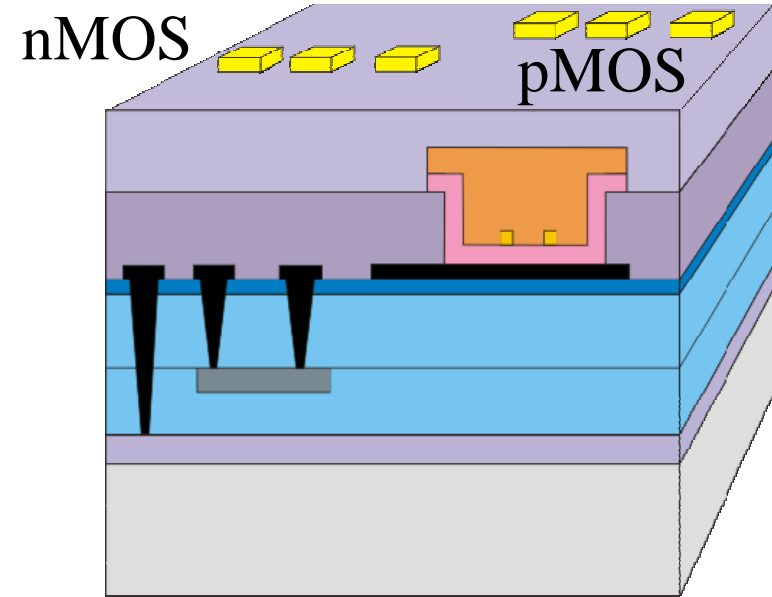
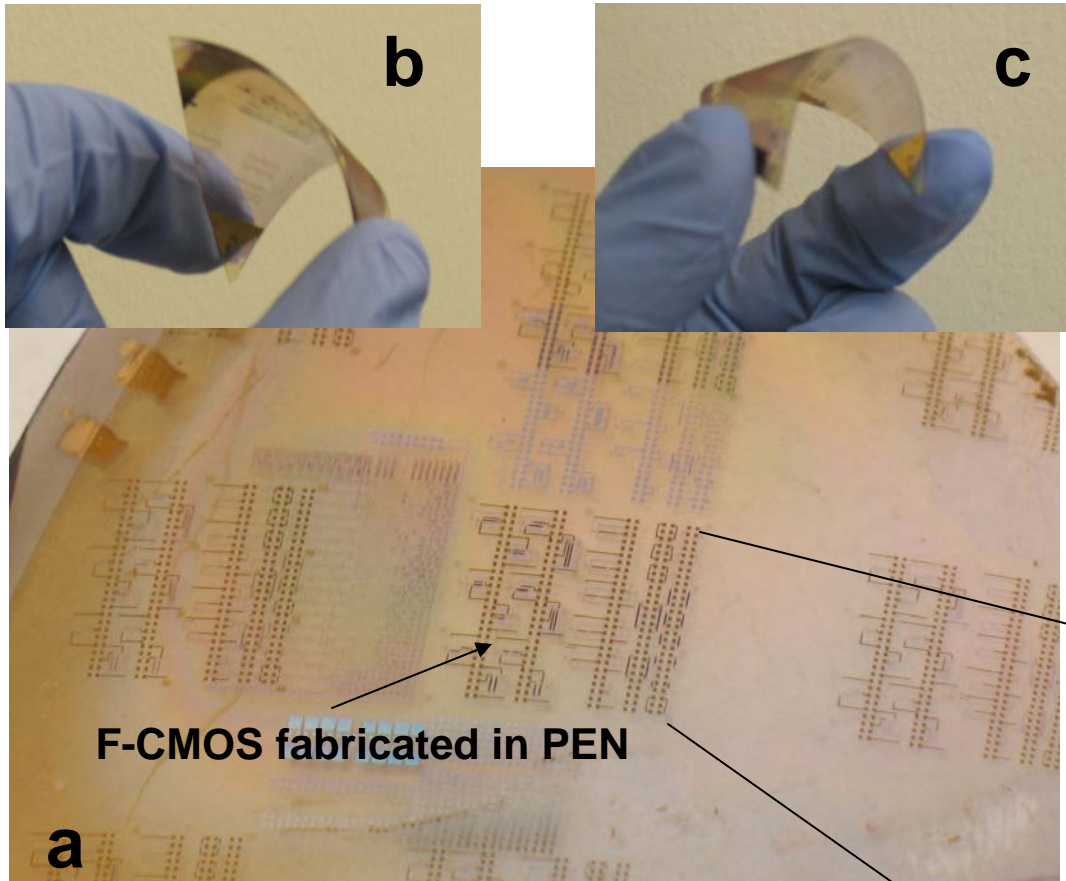
Why CMOS

- Dramatically reduced power consumption
- Analog circuitry possible with CMOS operational amplifiers

Flexible CMOS

- N-Type a-Si:H TFTs (FDC)
- P-type OTFT based (UTD)
- OTFTs fabricated after a-Si:H TFTs
- Standard Cell Approach

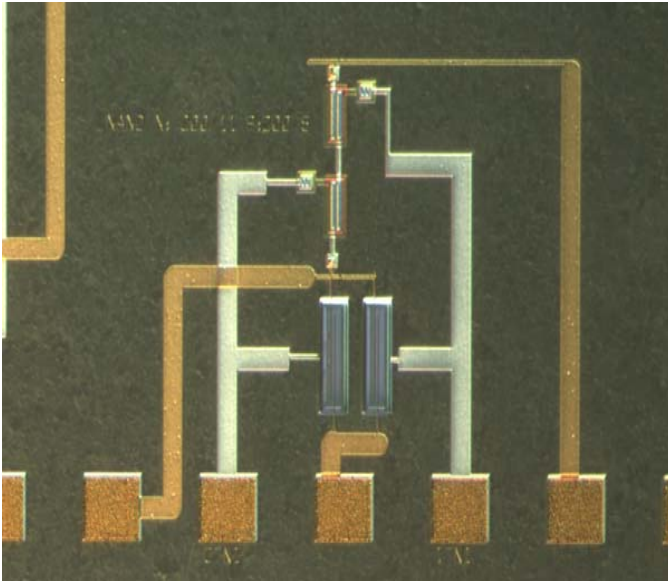




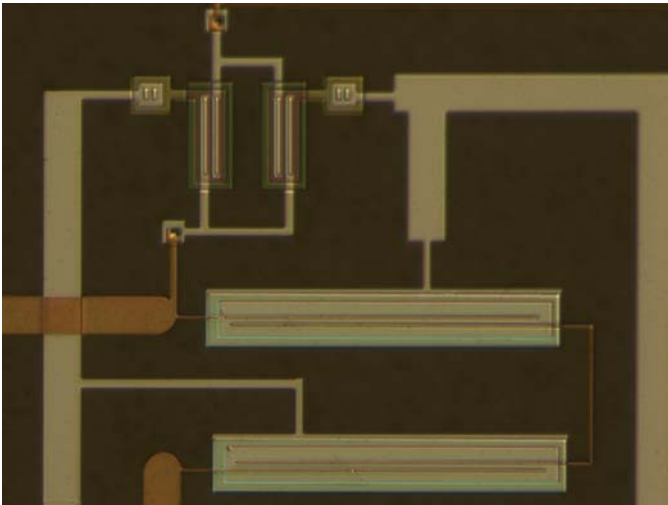
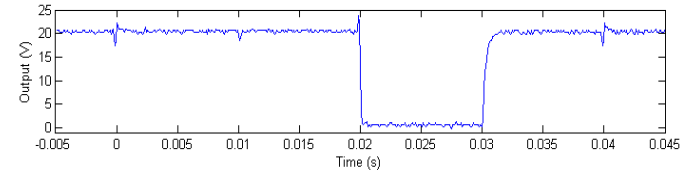
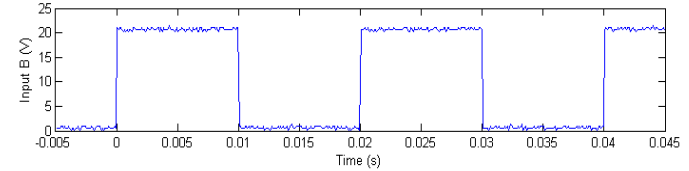
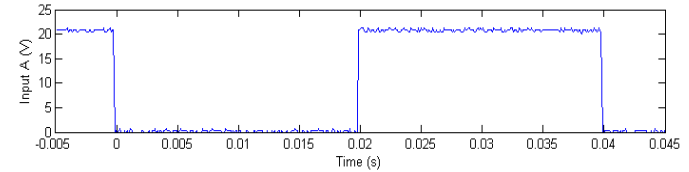
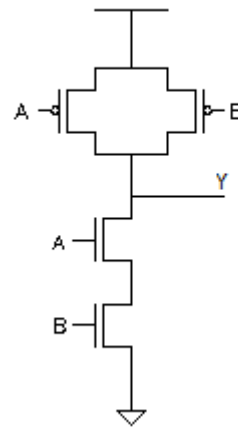
Layout

F-CMOS fabricated in PEN

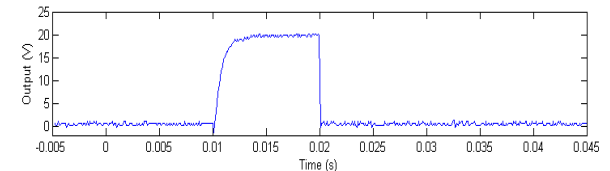
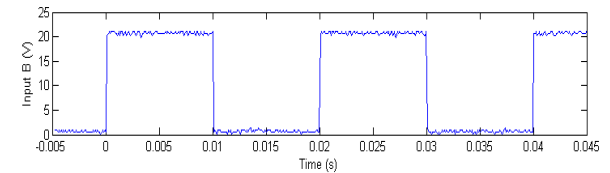
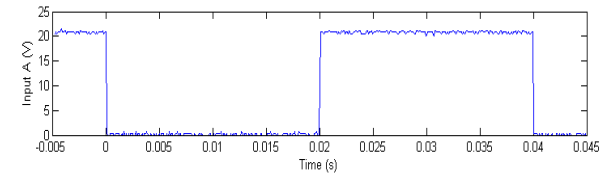
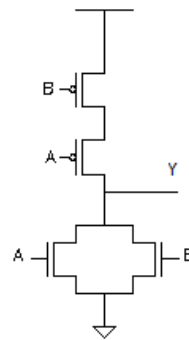
- Die consists of logic gates, inverters and ring oscillators
- All processing Temperature < 180C
- Die size ~ 0.75 cm²

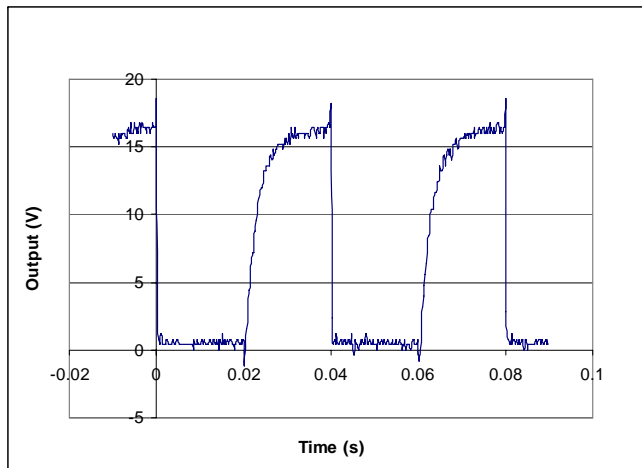
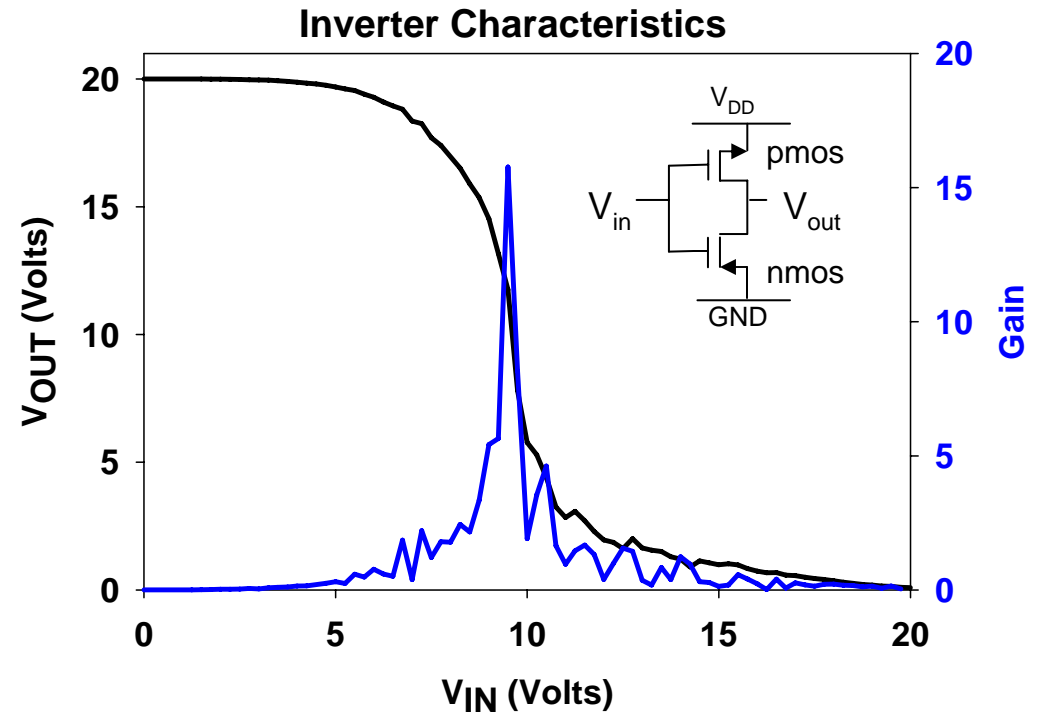
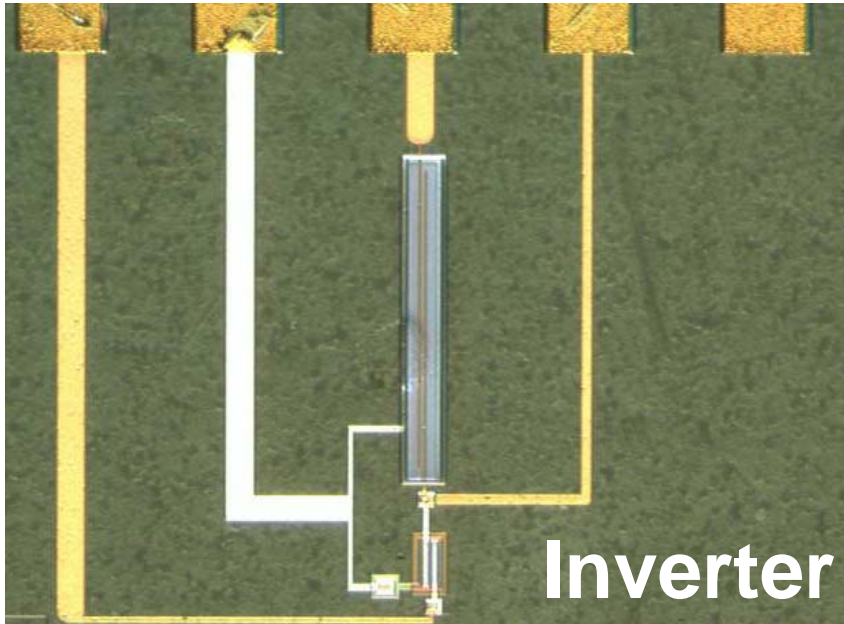


NAND Gate



NOR Gate

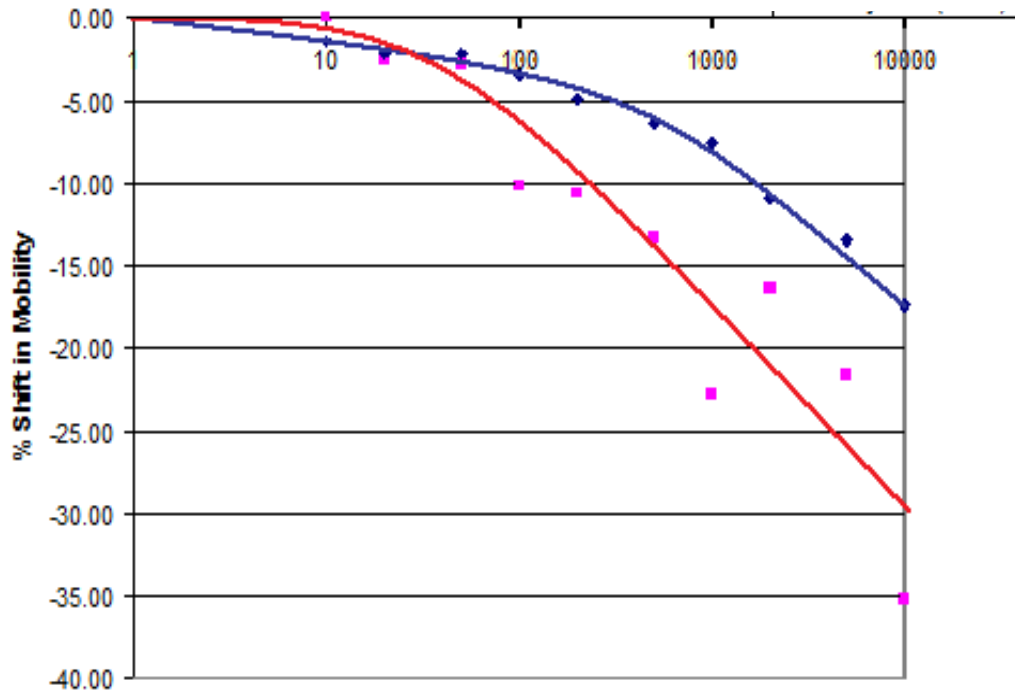




- Inverter swings rail-rail
- Inverter Gain ~ 16 at $V_{DD}/2$
- $V_{DD} = 20V$

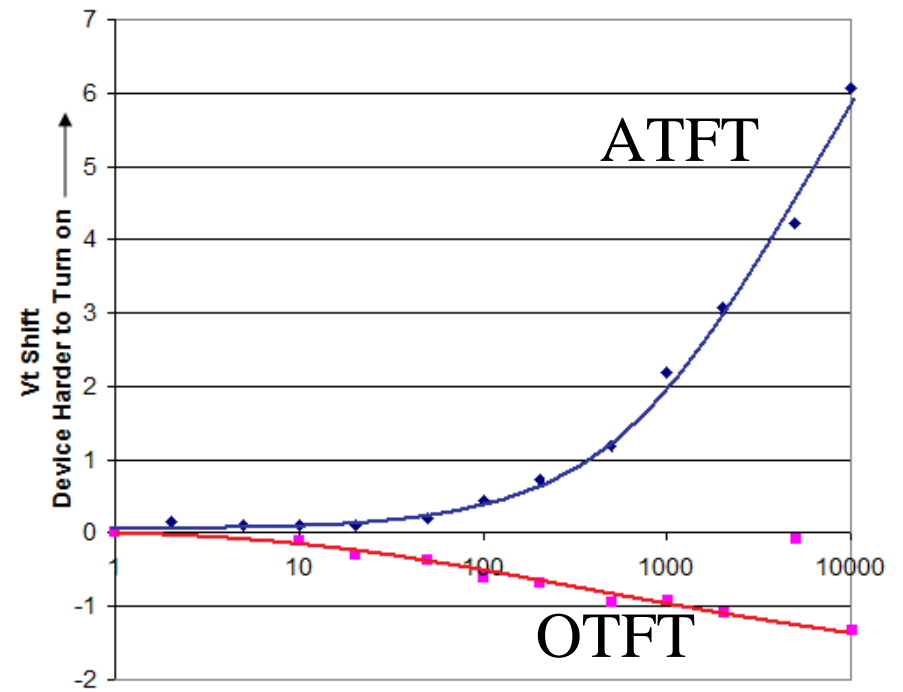
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- Summary

Mobility Shift vs log Time



Log(t)

Threshold Voltage Degradation vs Log Time

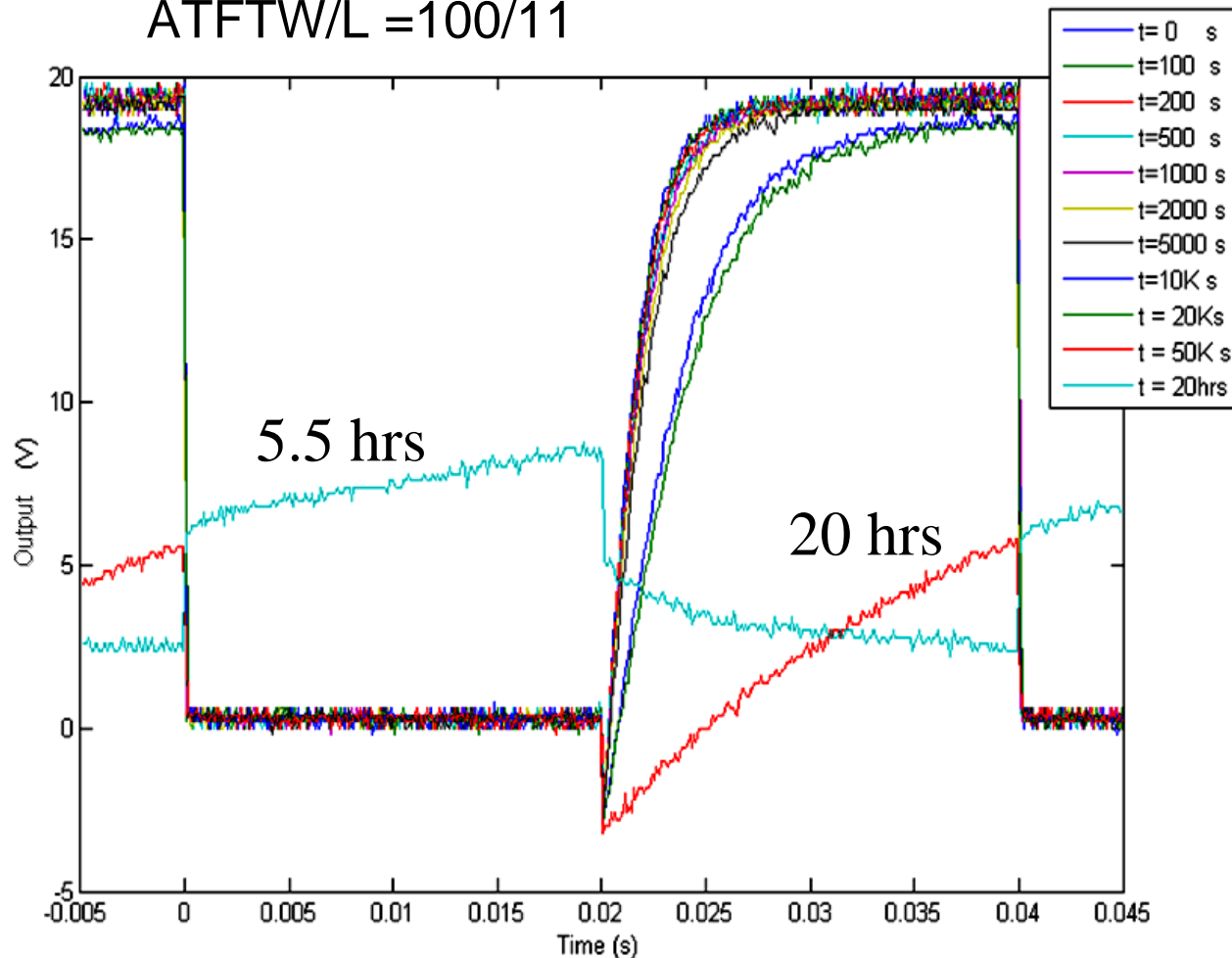


Log(t)

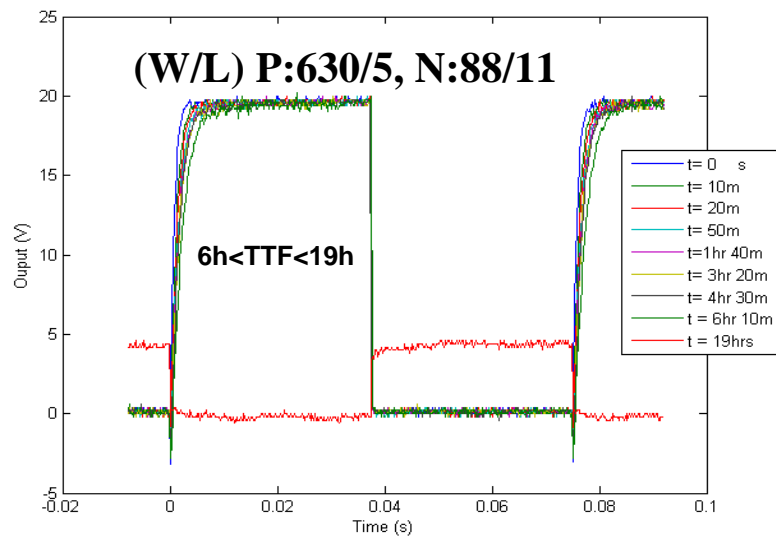
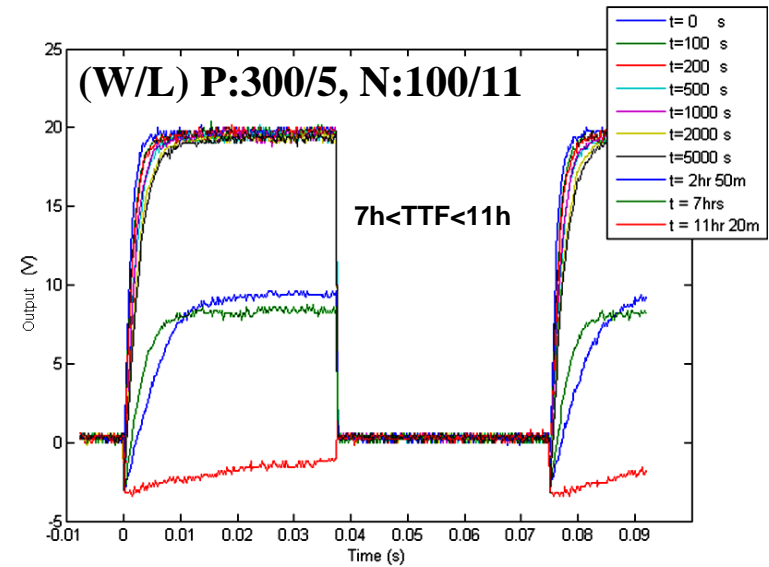
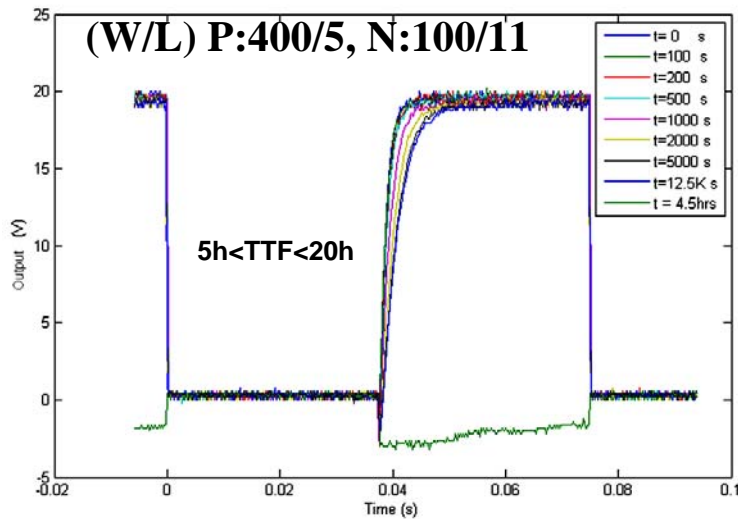
- OTFT mobility decreases from 0.083 cm²/V-s to 0.053 cm²/V-s (**35%**)
- ATFT mobility decreases from 0.354 cm²/Vs to 0.298 cm²/V-s (**15%**)
- OTFT V_T shifts in the positive direction → Easier to turn on
- ATFTs V_T shifts in the positive direction → Harder to turn on.

OTFT WL= 200/5

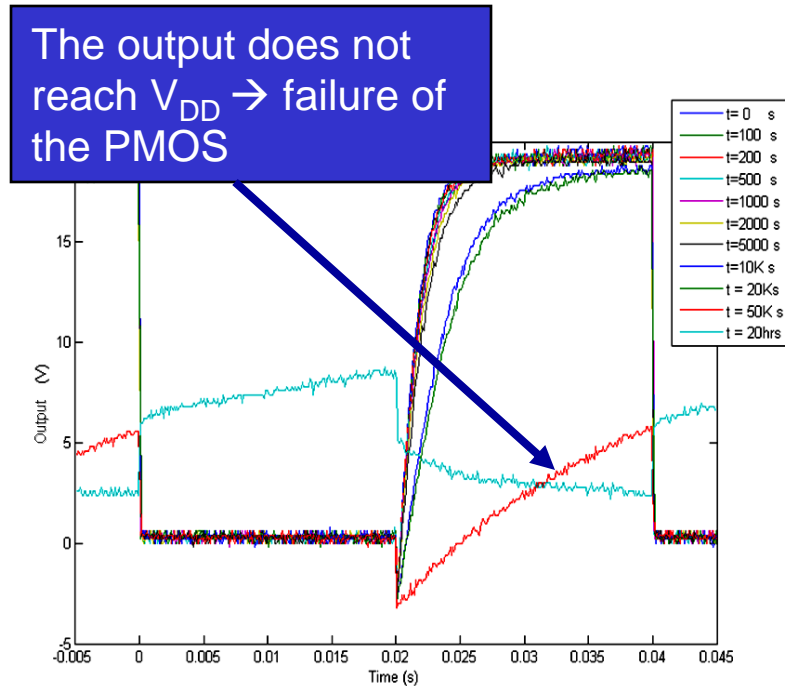
ATFTW/L =100/11



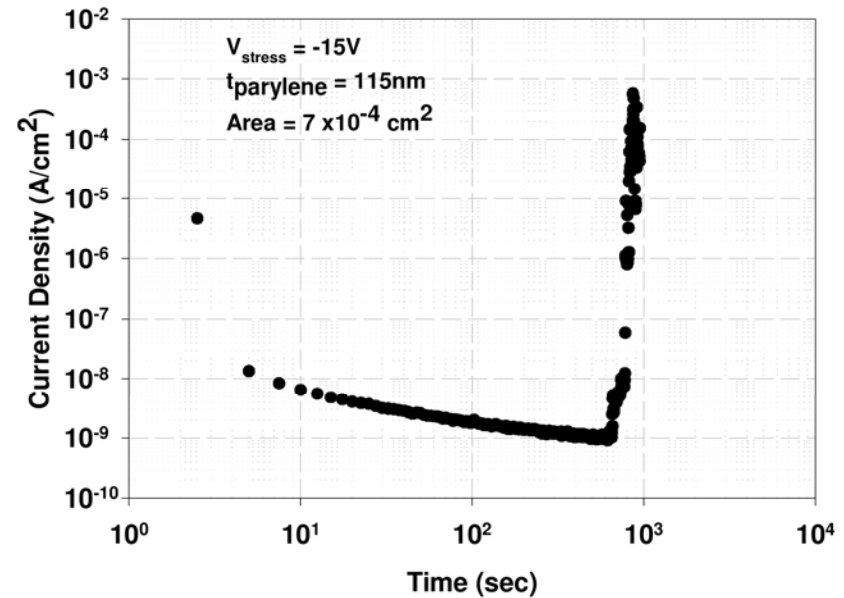
- Inverter subjected to 50% duty cycle
 - 40 ms period, 20V p-p pulse waveform, at $V_{DD}=20V$
- failure of the device happens in between 5.5-20hrs



- Transient output of several CMOS on Flexible substrates
- All devices failed between 7-20hrs



TDDDB for Parylene Gate Dielectric



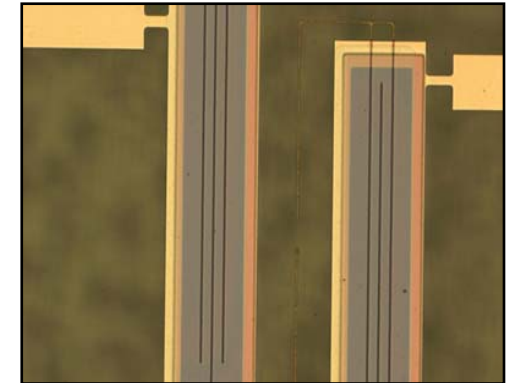
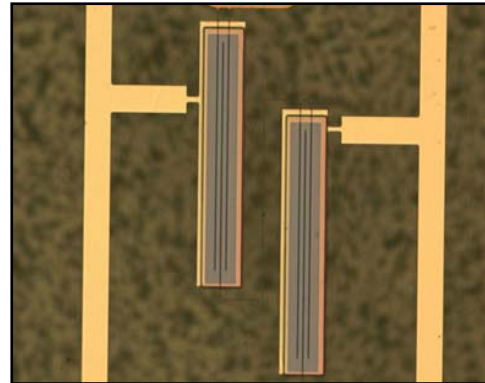
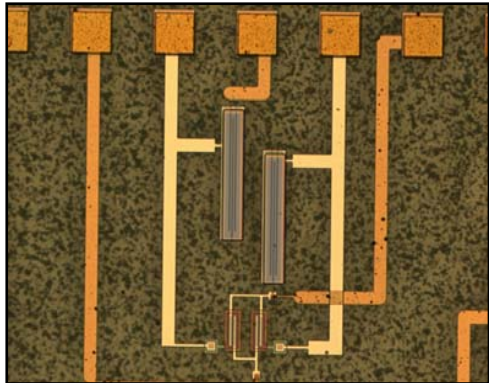
- Gate dielectric (OTFT) likely breaking down after stress

NAND Gates

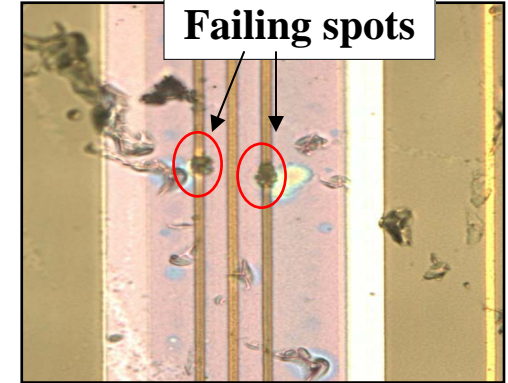
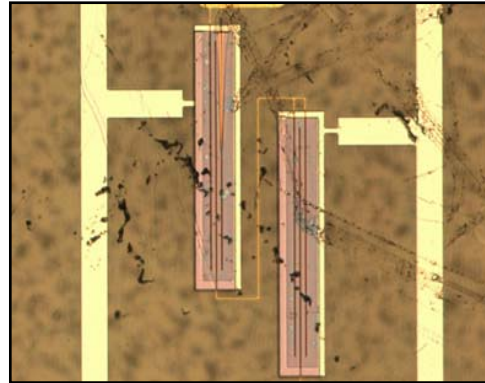
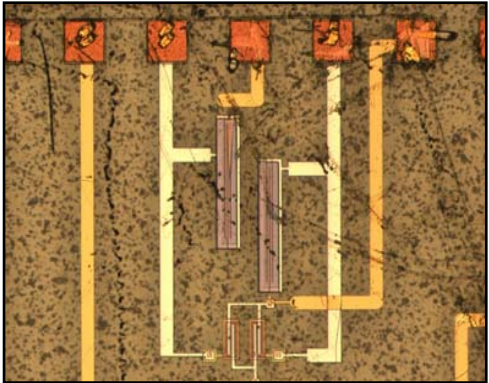


Increasing Magnification

Not Stressed

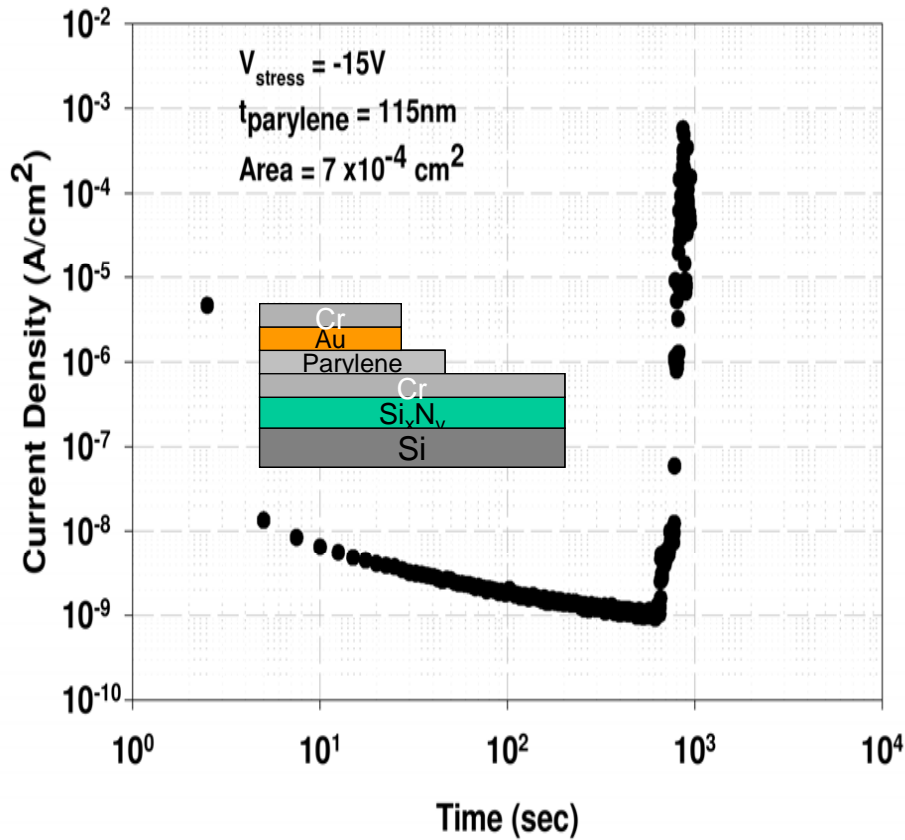


Stressed



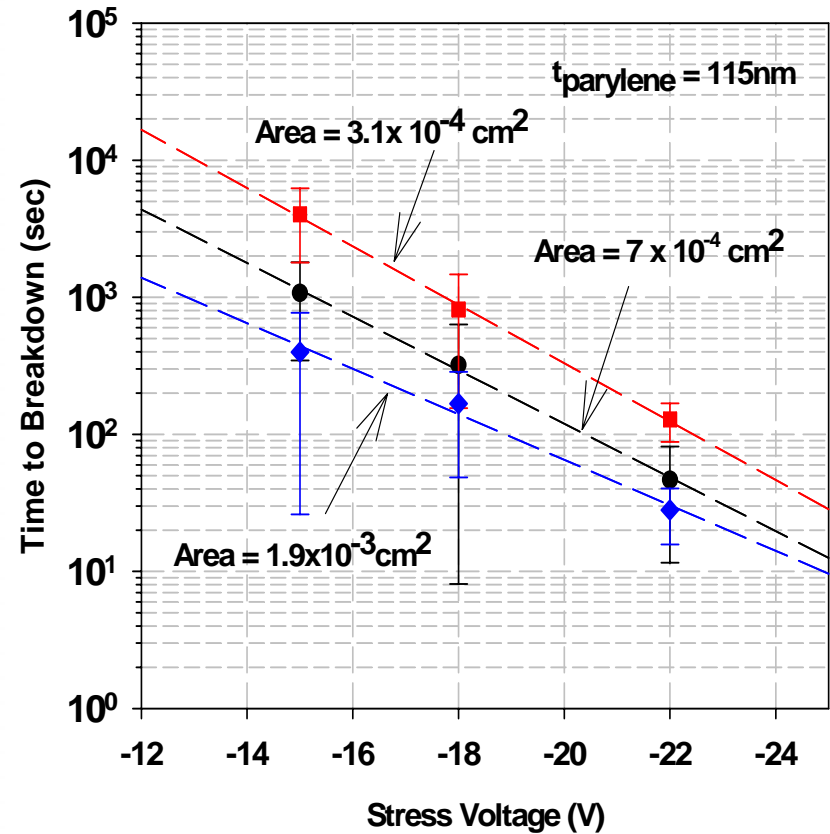
- Source of gate dielectric breakdown likely due to defects in the dielectric
- Currently evaluating alternate organic, inorganic and hybrid dielectrics to improve gate dielectric reliability

Typical Results



- Time to breakdown $\sim 10\times$ initial current
- Area dependence \longrightarrow defects dominated

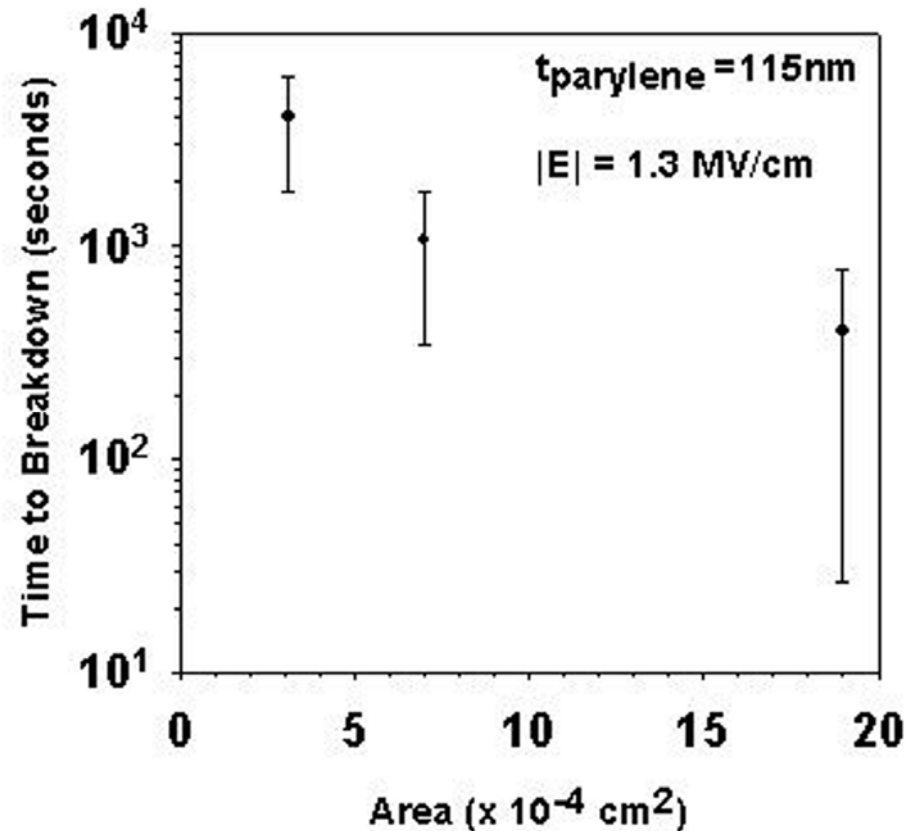
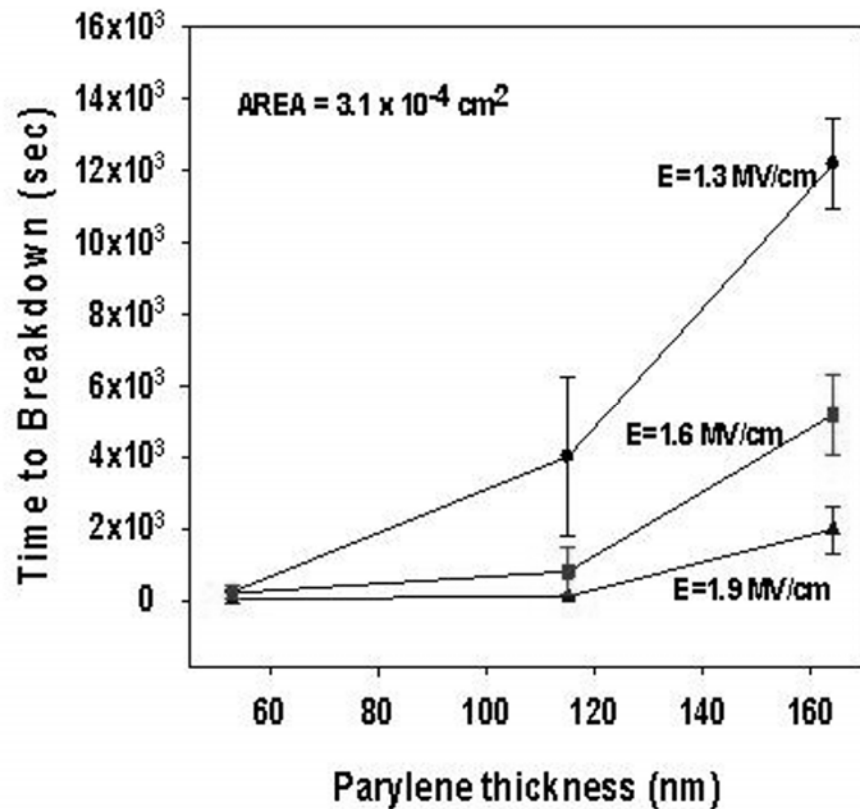
TDDB as Function of Device Area



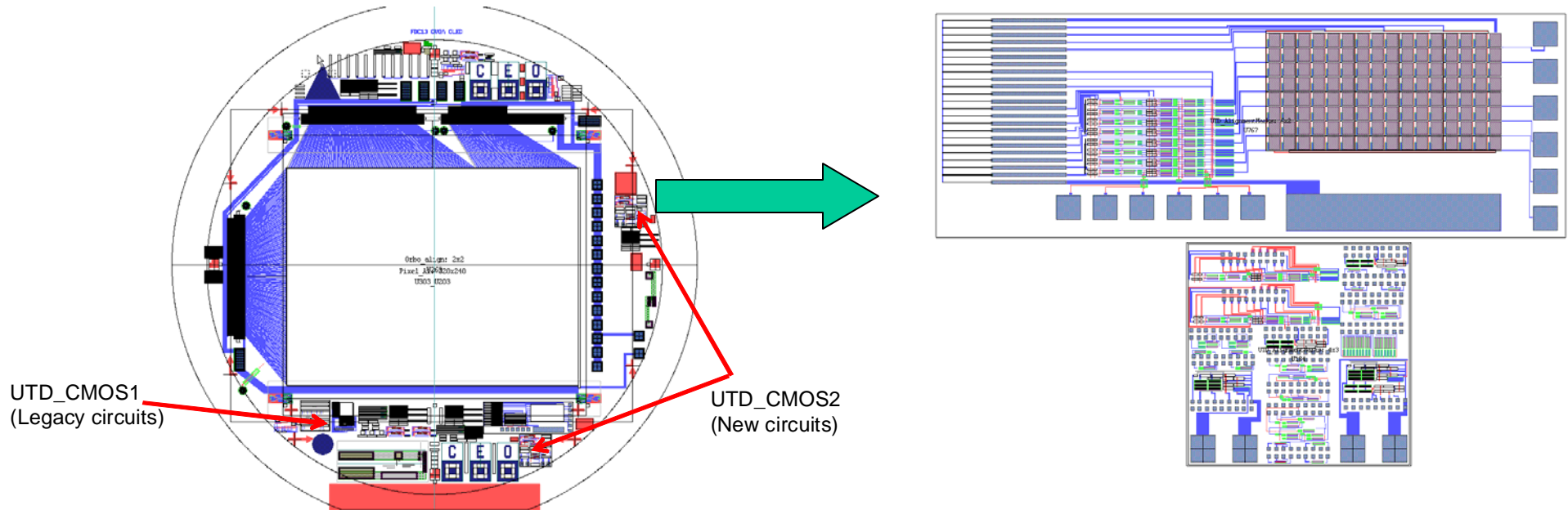
$$t_f \propto V^{-n}$$

$$n \sim 5-9$$

n - strongly depends on area and thickness



- TDDB of thin parylene show field dependence
 - Predominantly determined by the number of defects
- Lifetime extracted from power law dependence > 1000hrs operating under stress conditions (W/L of $1000\mu\text{m}/6\mu\text{m}$ and fixed gate bias of -10V)



■ Legacy circuits

- nMOS, pMOS TFTs
- Inverters
- NANDs
- NORs

■ New Circuits

- Opamp
- Integrated column drivers
- Column drivers with 16x8 display
- Ring oscillators
- Latches and FlipFlops

- CMOS circuits on flexible substrate have been demonstrated
 - **nMOS a-Si:H** (maximum processing temperature <180C)
 - **pMOS Pentacene** (maximum processing temperature <120C)
- Inverters (gain of 16) and two input NAND and NOR gates with logic function demonstrated
- Electrical stress degradation of the CMOS circuits indicates that gate dielectric (pMOS) causes device failure
 - Currently evaluating alternate gate dielectrics for pMOS
- CMOS devices currently under fabrication include:
 - Op-amp, Bias circuit, Integrated column drivers, column drivers, ring oscillators, latches and flipflops